

X Wallart

List of Publications by Year in descending order

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29
papers

1,249
citations

394421

19
h-index

477307

29
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29
all docs

29
docs citations

29
times ranked

1504
citing authors

#	ARTICLE	IF	CITATIONS
1	Two-dimensional Rutherford-like scattering in ballistic nanodevices. <i>Physical Review B</i> , 2018, 98, .	3.2	3
2	NanoARPES of twisted bilayer graphene on SiC: absence of velocity renormalization for small angles. <i>Scientific Reports</i> , 2016, 6, 27261.	3.3	28
3	Formation of quantum dots in the potential fluctuations of InGaAs heterostructures probed by scanning gate microscopy. <i>Physical Review B</i> , 2015, 91, .	3.2	7
4	Probing the electronic properties of graphene on C-face SiC down to single domains by nanoresolved photoelectron spectroscopies. <i>Physical Review B</i> , 2015, 92, .	3.2	12
5	High-resolution angle-resolved photoemission spectroscopy study of monolayer and bilayer graphene on the C-face of SiC. <i>Physical Review B</i> , 2013, 88, .	3.2	22
6	Coherent tunnelling across a quantum point contact in the quantum Hall regime. <i>Scientific Reports</i> , 2013, 3, 1416.	3.3	26
7	Scanning gate spectroscopy of transport across a quantum Hall nano-island. <i>New Journal of Physics</i> , 2013, 15, 013049.	2.9	19
8	Transport Inefficiency in Branched-Out Mesoscopic Networks: An Analog of the Braess Paradox. <i>Physical Review Letters</i> , 2012, 108, 076802.	7.8	44
9	On the imaging of electron transport in semiconductor quantum structures by scanning-gate microscopy: successes and limitations. <i>Semiconductor Science and Technology</i> , 2011, 26, 064008.	2.0	73
10	High yield of self-catalyzed GaAs nanowire arrays grown on silicon via gallium droplet positioning. <i>Nanotechnology</i> , 2011, 22, 275602.	2.6	146
11	Graphene growth by molecular beam epitaxy using a solid carbon source. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2010, 207, 300-303.	1.8	86
12	Graphene growth by molecular beam epitaxy on the carbon-face of SiC. <i>Applied Physics Letters</i> , 2010, 97, .	3.3	80
13	Gold-free GaAs/GaAsSb heterostructure nanowires grown on silicon. <i>Applied Physics Letters</i> , 2010, 96, .	3.3	83
14	Imaging Coulomb islands in a quantum Hall interferometer. <i>Nature Communications</i> , 2010, 1, 39.	12.8	60
15	Atomic scale flattening, step formation and graphitization blocking on 6H- and 4H-SiC{0 0 0 1} surfaces under Si flux. <i>Semiconductor Science and Technology</i> , 2009, 24, 125014.	2.0	20
16	Comparative Sb and As segregation at the InP on GaAsSb interface. <i>Applied Physics Letters</i> , 2008, 93, .	3.3	9
17	Kinetics, stoichiometry, morphology, and current drive capabilities of Ir-based silicides. <i>Journal of Applied Physics</i> , 2007, 102, .	2.5	11
18	Imaging Electron Wave Functions Inside Open Quantum Rings. <i>Physical Review Letters</i> , 2007, 99, 136807.	7.8	65

#	ARTICLE	IF	CITATIONS
19	Imaging and controlling electron transport inside a quantum ring. <i>Nature Physics</i> , 2006, 2, 826-830.	16.7	73
20	Dwell-Time-Limited Coherence in Open Quantum Dots. <i>Physical Review Letters</i> , 2005, 94, 146802.	7.8	47
21	Transmission electron microscopy of iridium silicide contacts for advanced MOSFET structures with Schottky source and drain. <i>Journal of Alloys and Compounds</i> , 2004, 382, 24-28.	5.5	1
22	Formation of platinum-based silicide contacts: Kinetics, stoichiometry, and current drive capabilities. <i>Journal of Applied Physics</i> , 2003, 94, 7801.	2.5	76
23	Long dephasing time and high-temperature conductance fluctuations in an open InGaAs quantum dot. <i>Physical Review B</i> , 2002, 66, .	3.2	27
24	XPS study of GaInP on GaAs interface. <i>Applied Surface Science</i> , 1998, 123-124, 523-527.	6.1	3
25	X-ray photoemission characterization of interface abruptness and band offset of Ga _{0.5} In _{0.5} P grown on GaAs. <i>Journal of Applied Physics</i> , 1998, 84, 2127-2132.	2.5	26
26	Kinetics and mechanism of low temperature atomic oxygen-assisted oxidation of SiGe layers. <i>Journal of Applied Physics</i> , 1998, 83, 2842-2846.	2.5	27
27	Plasma assisted oxidation of SiGe layers at 500°C: interface characterization. <i>Applied Surface Science</i> , 1996, 104-105, 385-391.	6.1	8
28	Germanium behaviour during the low-temperature plasma-assisted oxidation of SiGe alloys. <i>Surface and Interface Analysis</i> , 1995, 23, 363-366.	1.8	3
29	Kinetic model of element III segregation during molecular beam epitaxy of III-V semiconductor compounds. <i>Applied Physics Letters</i> , 1995, 66, 52-54.	3.3	164